



Multimedia Available: Applied Materials Redefines Dielectric Etch Technology for Advanced Copper/Low k Chip Designs

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--(BUSINESS WIRE)--

Applied Materials Inc. redefines dielectric etch technology with its new Enabler(TM) Centura(R) system, the industry's first production etcher engineered for the complex and demanding requirements of 65nm devices, with extendibility to both future and earlier technologies.

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